

	Hits	Search Text	DBs
22	3	((multiple or pluralit\$4 or double) same (expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or defocus\$4 or offset\$4)) and ((expos\$4 or irradiat\$4 or illuminat\$4) near22 (pluralit\$4 or multiple or numerous) near26 (resolut\$4 or resol\$5 or complet\$4 or full\$2) near27 (amount or magnitude or variat\$4 or adjust\$4 or vary\$4)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5))) same (stepper or (step\$3 near9 repeat\$4))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
23	0	((multiple or pluralit\$4 or double) same (expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or defocus\$4 or offset\$4 or (step\$4 near8 repeat\$4))) and ((expos\$4 or irradiat\$4 or illuminat\$4) near22 (pluralit\$4 or multiple or numerous) near26 (overlap\$4 or super\$4impos\$4) same (amount or adjust\$4 or adjust\$4) same (mask or reticle or photomask) same (meandering or rag\$3 or irregular\$6)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5))) same (stepper or (step\$3 near9 repeat\$4))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
24	0	((multiple or pluralit\$4 or double) same (expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or defocus\$4 or offset\$4 or (step\$4 near8 repeat\$4))) and ((expos\$4 or irradiat\$4 or illuminat\$4) near22 (pluralit\$4 or multiple or numerous) near26 (overlap\$4 or super\$4impos\$4) same (amount or adjust\$4 or adjust\$4) same (mask or reticle or photomask) same (meandering or ragg\$3 or irregular\$6)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (scan\$5 or sweep or pass\$3 or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5))) same (stepper or (step\$3 near9 repeat\$4))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	0	((multiple or pluralit\$4 or double or dual) same (expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or scan\$4 or defocus\$4 or offset\$4 or (step\$4 near8 repeat\$4))) and ((expos\$4 or irradiat\$4 or illuminat\$4) near22 (pluralit\$4 or multiple or numerous) near26 (overlap\$4 or super\$4impos\$4) same (amount or adjust\$4 or adjust\$4) same (mask or reticle or photomask) same (meandering or rag\$3 or irregular\$6)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (scan\$5 or sweep or pass\$3 or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5))) same (stepper or (step\$3 near9 repeat\$4)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
26	17	((multiple or pluralit\$4 or double or dual) same (expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or scan\$4 or defocus\$4 or offset\$4 or (step\$4 near8 repeat\$4))) and ((expos\$4 or irradiat\$4 or illuminat\$4) near22 (pluralit\$4 or multiple or numerous) near26 (overlap\$4 or super\$4impos\$4) same (amount or adjust\$4 or adjust\$4) same (mask or reticle or photomask)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (scan\$5 or sweep or pass\$3 or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5))) same (stepper or (step\$3 near9 repeat\$4)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
27	6	((multiple or pluralit\$4 or double or dual) same (expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (defocus\$4 or offset\$4 or deflect\$4)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (plural\$5 or multiple or dual or double) same (amount or adjust\$4 or var\$5) same (less\$3 or partial\$4) same (mask or reticle or photomask) same (shot or region or area) same (photoresist or resist or photosensitive)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (scan\$5 or sweep or pass\$3 or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5))) same (stepper or (step\$3 near9 repeat\$4)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	13	((multiple or pluralit\$4 or double or dual) same (expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or scan\$4 or defocus\$4 or offset\$4 or (step\$4 near8 repeat\$4))) and ((expos\$4 or irradiat\$4 or illuminat\$4) near22 (pluralit\$4 or multiple or numerous) near26 (overlap\$4 or super\$4impos\$4) same (amount or adjust\$4 or adjust\$4) same (mask or reticle or photomask)) and ((pattern or develop\$4) same (electroplat\$4 or plat\$4) same (substrate or wafer or circuit\$4) same (master or mold or mask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
29	1	((expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or scan\$4 or defocus\$4 or offset\$4 or (step\$4 near8 repeat\$4))) and (((expos\$4 or irradiat\$4 or illuminat\$4) near26 (overlap\$4 or super\$4impos\$4 or scan\$4 or step\$6repeat)) same (amount or adjust\$4 or adjust\$4) same (mask or reticle or photomask) same (offset or defocus\$4)) and ((pattern or develop\$4) same (electroplat\$4 or plating) same (substrate or wafer) same (master or mold or mask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	9	((expos\$4 or illuminat\$4 or irradiat\$4) same (photoresist or photosensitive or resist) same (step\$4 or sweep\$4 or repeat\$4 or scan\$4 or defocus\$4 or offset\$4 or (step\$4 near8 repeat\$4))) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (mask or reticle or photomask) same (offset or defocus\$4)) and ((mask or photomask) same (gr\$2y near3 scale)) and (HEBS or (high near3 energy near3 beam near3 sensitive))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB